

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S14 5	2	"5442561".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 18:59
S14 6	786	organic with (photomask\$3 or photo-mask\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:02
S14 7	818	(mass near2 production) with (exposure or lithography)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:02
S14 8	5	((mass near2 production) with (exposure or lithography)) and (700/121.ccls.)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:02
S14 9	420	organic\$4 with (photomask\$3 or photo-mask\$3 or mask\$3) with resin with (photo or EUV or UV or ultra-violet or light or lightsource or photolithograph\$6 or photosensit\$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:02
S15 0	160	(organic\$4 with (photomask\$3 or photo-mask\$3 or mask\$3) with resin with (photo or EUV or UV or ultra-violet or light or lightsource or photolithograph\$6 or photosensit\$6)) and ("700"/\$.ccls. or "702"/\$.ccls. or "438"/\$.ccls. or "716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:02
S15 1	2228	(mass near2 production) with (exposure or lithography or photomask\$3 or photo-mask\$3 or mask\$3 or resist or photo-resist or photolithograph\$6 or stepper)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:02
S15 2	3246	(mass near2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) with (exposur\$3 or lithograph\$6 or photomask\$3 or photo-mask\$3 or mask\$3 or resist or photo-resist or photolithograph\$6 or stepper or photo-lithograph\$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:03

S15 3	10	((organic\$4 with (photomask\$3 or photo-mask\$3 or mask\$3) with resin with (photo or EUV or UV or ultra-violet or light or lightsource or photolithograph\$6 or photosensit\$6)) and ("700"/\$.ccls. or "702"/\$.ccls. or "438"/\$.ccls. or "716"/\$.ccls. or "430"/\$.ccls.)) and ((mass near2 (produc\$4 or manufatur\$4 or fabricat\$4 or making)) with (exposur\$3 or lithograph\$6 or photomask\$3 or photo-mask\$3 or mask\$3 or resist or photo-resist or photolithograph\$6 or stepper or photo-lithograph\$6))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:03
S15 4	15	((mass near2 (produc\$4 or manufatur\$4 or fabricat\$4 or making)) with (exposur\$3 or lithograph\$6 or photomask\$3 or photo-mask\$3 or mask\$3 or resist or photo-resist or photolithograph\$6 or stepper or photo-lithograph\$6)) and (700/121.ccls.)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:03
S15 5	69	257/390.ccls. and (organic or polymer or resin or polyimide or phenolic or acrylic)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:03
S15 6	28852	(photomask\$3 or photo-mask\$3 or mask\$3) near3 (type or kind or class or (metal and (organic or polymer or resin or polyimide or phenolic or acrylic)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:03
S15 7	1582	((photomask\$3 or photo-mask\$3 or mask\$3) with ((batch or lot) near2 (produc\$4 or manufatur\$4 or fabricat\$4 or making))) or ((photomask\$3 or photo-mask\$3 or mask\$3) with (mass adj2 (produc\$4 or manufatur\$4 or fabricat\$4 or making)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:03

S15 8	223	((organic or resin or polyimide or phenolic or acrylic) with (photosensit\$5 or photolacquer or photo-lacquer or photo-lithograph\$6 or photolithograph\$6 or expos\$4 or radiation or UV or EUV or shield\$4 or block\$4 or sheild\$4))) and (((photomask\$3 or photo-mask\$3 or mask\$3) with ((batch or lot) near2 (produc\$4 or manufatur\$4 or fabricat\$4 or making))) or ((photomask\$3 or photo-mask\$3 or mask\$3) with (mass adj2 (produc\$4 or manufatur\$4 or fabricat\$4 or making))))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:03
S15 9	112	("700"/\$.ccls. or "702"/\$.ccls. or "438"/\$.ccls. or "716"/\$.ccls. or "430"/\$.ccls. or "216"/\$.ccls. or "257"/\$.ccls.) or 382/144.ccls.) and (((((organic or resin or polyimide or phenolic or acrylic) with (photosensit\$5 or photolacquer or photo-lacquer or photo-lithograph\$6 or photolithograph\$6 or expos\$4 or radiation or UV or EUV or shield\$4 or block\$4 or sheild\$4))) and (((photomask\$3 or photo-mask\$3 or mask\$3) with ((batch or lot) near2 (produc\$4 or manufatur\$4 or fabricat\$4 or making))) or ((photomask\$3 or photo-mask\$3 or mask\$3) with (mass adj2 (produc\$4 or manufatur\$4 or fabricat\$4 or making)))))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:03
S16 0	598590	"700"/\$.ccls. or "702"/\$.ccls. or "438"/\$.ccls. or "716"/\$.ccls. or "430"/\$.ccls. or "216"/\$.ccls. or "257"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:04
S16 1	661569	((metal or aluminum or alloy or chrom\$6 or metallic) near3 (membrane or film or resist or resin or laminate or photomask\$3 or photo-mask\$3 or mask\$3 or pellicle or coat\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:10

S16 2	132804	(photoresist or photo-resist or ((organic\$4 or polyimide or Cellulose or Acetate or Nitrocellulose) near3 (membrane or film or resist or resin or laminate or photomask\$3 or photo-mask\$3 or mask\$3 or pellicle or coat\$4))) same (lithograph\$6 or litho-graph\$6 or photo-lithograph\$6 or mask\$4 or photo-mask\$3 or photomask\$3 or exposure or ebeam or e-beam or (energy near2 beam) or laser or (light near3 pattern\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:04
S16 3	833	702/81-84.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:04
S16 4	3512	700/28,32,95,97,102,103,104, 108-110.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:04
S16 5	4360	700/28,32,95,97,102,103,104, 108-110,121.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:04
S16 6	4182	S163 or S164	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:04
S16 7	5005	S163 or S165 or S166	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:05
S16 8	12725	((mask) with (light\$3 or laser\$4 or laser-beam or photo or photo-lithograph\$6 or photolithograph\$6)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:12
S16 9	3291	(photomask\$3 or photo-mask\$3).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:08

S17 0	1418890	(metal or aluminum or alloy or chrom\$6 or metallic or organic or polymer or resin or polyimide or phenolic or acrylic) near3 (membrane or film or resist or resin or laminate or photomask\$3 or photo-mask\$3 or mask\$3 or pellicle or coat\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:11
S17 1	1465843	(metal or aluminum or alloy or chrom\$6 or metallic or organic or polymer or resin or polyimide or phenolic or acrylic or organic\$4 or Cellulose or Acetate or Nitrocellulose) near3 (membrane or film or resist or resin or laminate or photomask\$3 or photo-mask\$3 or mask\$3 or pellicle or coat\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:13
S17 2	13158	((mask) with (light\$3 or laser\$4 or laser-beam or photo or photo-lithograph\$6 or photolithograph\$6 or uv or euv or ultraviolet or ultra-violet)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:13
S17 3	15308	S168 or S169	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:13
S17 4	7280	S171 and S173	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:14
S17 5	23	S167 and S174	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:39
S17 6	4740	S160 and S174	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:52
S17 7	3	"4409319".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:52

S17 8	28285	resist adj2 mask	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 20:06
S17 9	1	S177 and S178	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 19:53
S18 0	2435	(resist adj2 mask).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 20:06
S18 1	2161	S160 and S180	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 20:06
S18 2	5	"5776836".pn. or "3767490".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 20:10
S18 3	0	S182 and reticle	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 20:10